

An accessible and applicable guide to quantitative problem solving in vacuum technology, this book is aimed at newcomers, students and the experienced practitioner. It contains essential information and worked examples for those using vacuum technology in chemical applications and who are involved in the design and operation of vacuum equipment.

Using step by step solutions of example calculations and formulae, ***Vacuum Technology: Calculations in Chemistry*** sets out to encourage readers to quantify their own systems so that they can ensure efficient operation and fault finding. Whilst emphasising the use of appropriate units in calculations and using well known expressions in vacuum technology throughout, the book includes:

- formulae necessary for quantitative vacuum technology
- commonly required data for common gases in tabulated form
- schematic diagrams of systems and layouts

This book is certain to be a confidence inspiring publication for use in both research and industry.

Dr David Hucknall joined Leybold Vacuum UK Ltd in 1986 and has unrivalled expertise in vacuum technology. Since 1991 he has represented the UK on the European Working Group responsible for drafting standards on leak detection. **Dr Alan Morris**, currently at the University of Southampton, has over 25 years experience in the field of gas phase UV photoelectron spectroscopy. He has contributed to the design and development of spectrometers for the study of unstable species using a wide range of radiation sources.

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